AMENDMENTS TO THE CLAIMS

The listing of claims will replace all prior versions and listings of claims in the application:

1-7. (Cancelled)

8. **(Currently Amended)** A method for manufacturing a glass substrate for an information recording medium, the manufacturing method comprising:

a first washing step for washing a surface of a disk-shaped glass plate with an acid washing liquid, wherein an altered surface layer is formed on the surface of the glass substrate by the first washing step; thereafter

a step for grinding the altered surface layer for a depth of 0.5 nm or more with abrasion grains so that the altered surface layer has a thickness of 3 nm or less; and thereafter

a second washing step for washing the surface with an alkaline washing liquid, wherein the altered surface layer formed by acidic washing in the first washing step is removed by the step for grinding and the second washing step.

- 9. (Previously Presented) The manufacturing method according to claim 8, wherein the removing step includes scrubbing the surface with a scrub member in a circumferential direction of the glass plate while supplying the surface with diamond abrasion grains.
- 10. (Previously Presented) The manufacturing method according to claim 8, wherein the first washing step includes immersing the glass plate in a strong acid solution and then immersing the glass plate in a strong alkaline solution.

Application No. 10/532,564 Amendment "E" dated October 1, 2009 Reply to Office Action mailed July 1, 2009

11. **(Currently Amended)** A method for manufacturing a glass substrate for an information recording medium, the manufacturing method comprising:

preparing a disk-shaped glass plate containing silicon oxide, aluminum oxide, and alkaline earth metal oxide with a uniform chemical composition;

polishing the glass plate to form a smooth surface;

immersing the glass plate in an acid solution to form an altered surface layer in which the ingredient ratio of at least one of aluminum oxide and alkaline earth metal oxide is decreased; thereafter

removing at least part of the altered surface layer with an abrasive to such that the altered surface layer has a thickness of 3 nm or less; and thereafter

uniformly etching the altered surface layer having a thickness of 3 nm or less while washing off the abrasive with an alkaline washing liquid.

- 12. **(Original)** The manufacturing method according to claim 11, wherein the acid solution is a strong acid solution having a pH of 3.0 or less.
- 13. **(Previously Presented)** The manufacturing method according to claim 12, wherein said forming a surface layer includes immersing the glass plate in the strong acid solution and then immersing the glass plate in a strong alkaline solution having a pH value of 10.5 or greater.
- (Previously Presented) The manufacturing method according to claim
 wherein said forming the surface layer includes removing adhered substances that are adhered on the smooth surface.
- 15. **(Original)** The manufacturing method according to claim 11, wherein the alkaline washing liquid is an alkaline solution having a pH of 11.0 to 13.0.
- 16. (Previously Presented) The manufacturing method according to claim 8, wherein the step for grinding is a texture formation step for forming a texture on the surface of the class plate.

Application No. 10/532,564 Amendment "E" dated October 1, 2009 Reply to Office Action mailed July 1, 2009

17. (Previously Presented) The manufacturing method according to claim 8, wherein the first washing step, the step for grinding, and the second washing step are controlled to adjust the thickness of the altered surface layer finally remained on the glass plate.

18. **(Previously Presented)** The manufacturing method according to claim 11, wherein said immersing, said removing, and said uniformly etching are controlled to adjust the thickness of the altered surface layer finally remained on the glass plate.

19. (Previously Presented) The manufacturing method according to claim 8, wherein the first washing step, the step for grinding, and the second washing step are sequentially performed.

20. (Previously Presented) The manufacturing method according to claim 8, wherein the glass substrate is made of a multi-component glass material selected from the group consisting of soda lime glass, aluminosilicate glass, borosilicate glass and crystallization glass.

21. **(Previously Presented)** The manufacturing method according to claim 8, wherein a chemical strengthening process is performed between any one of the first washing step, the step for grinding, and the second washing step.

22. **(Previously Presented)** The manufacturing method according to claim 8, wherein the first washing step includes immersing the glass substrate in a strong acid washing liquid having a pH of 3.0 or less and then immersing the glass substrate in a strong alkaline solution having a pH of 10.5 or greater.

Application No. 10/532,564 Amendment "E" dated October 1, 2009 Reply to Office Action mailed July 1, 2009

- 23. (Previously Presented) The manufacturing method according to claim 22, wherein the immersing in a strong acid washing liquid and the immersing in a strong alkaline solution are performed for the same immersion time period under the same temperature.
- 24. **(Previously Presented)** The manufacturing method according to claim 23, wherein the first washing step includes immersing the glass substrate in 0.01% of a hydrofluoric acid solution for three minutes under a temperature of 35°C and then immersing the glass substrate in 0.01% of a potassium hydroxide solution for three minutes under a temperature of 35°C.
- 25. (Previously Presented) The manufacturing method according to claim 11, wherein the immersing step, the removing step and the uniformly etching step are sequentially performed.
- 26. (New) The manufacturing method according to claim 8, wherein a deviation rate of surface roughness Ra of the glass substrate is less than or equal to 3%.
- (New) The manufacturing method according to claim 11, wherein a
 deviation rate of surface roughness Ra of the glass substrate is less than or equal to
 3%.